

## **REMARKS/ARGUMENTS**

Claims 16-20 stand rejected under 35 U.S.C. 102(b) as being anticipated by Downey; claim 16 stands rejected under 35 U.S.C. 102(b) as being anticipated by Kato.

Claim 16 comprises the limitations of implanting at least a halogen species within an at least partially formed semiconductor device to form at least one amorphous region; doping at least a portion of the at least one amorphous region to form at least one junction within the at least partially formed semiconductor device; and activating the doped portion of the at least one amorphous region of the at least partially formed semiconductor device by solid phase epitaxial re-growth. The invention as claimed in claim 16 requires the implanted halogen species to form at least one amorphous region. The Downey reference carefully distinguishes between implanting fluorine into an amorphous region and forming the amorphous region. In the office action dated 5/6/2004, the examiner emphasizes this point by carefully stating that "fluorine ions are implanted into amorphous region of the semiconductor, wherein amorphous region resulted from boron implantation (see col.3, lines 1-6)." Applicant agrees with the examiner on this point and therefore all the limitations of claim 16 are not contained in the Downey reference. The Downey reference is not a valid 102(b) reference and claim 16 is allowable over the cited art.

With regard to the Kato reference, the examiner again carefully explains that chlorine is implanted into amorphous regions since Kato teaches chlorine ions are implanted after the implantation of dopant ions. From the above discussion, all the limitations of claim 16 are not contained in the Kato reference. The Kato reference is not a valid 102(b) reference and claim 16 is allowable over the cited art.

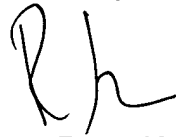
Claims 17-20 depend on claim 16 and therefore contain all the limitations of claim 16. Claims 17-20 are therefore also allowable over the cited art.

In light of the above, it is respectfully submitted that the present application is in condition for allowance, and notice to that effect is respectfully requested.

While it is believed that the instant response places the application in condition for allowance, should the Examiner have any further comments or suggestions, it is respectfully requested that the Examiner contact the undersigned in order to expeditiously resolve any outstanding issues.

To the extent necessary, Applicant petitions for an Extension of Time under 37 CFR 1.136. Please charge any fees in connection with the filing of this paper, including extension of time fees, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668.

Respectfully submitted,

A handwritten signature in black ink, appearing to read 'P. McLarty', with a long horizontal line extending to the right.

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